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**MOLECULAR IMPRINTS LEADS JOINT VENTURE TO \$36M NIST
ADVANCED TECHNOLOGY PROGRAM AWARD**

Austin, TX, May 5, 2004 – Molecular Imprints, Inc. (MII), the leading manufacturer of step and flash imprint lithography (S-FIL™) equipment, announces today that a \$36M joint venture proposal has been funded by the National Institute of Standards and Technology – Advanced Technology Program (NIST ATP) for the development of nano-imprint lithography at key semiconductor roadmap nodes. The other joint venture partners include KLA-Tencor, Photronics, Motorola Labs, and the University of Texas at Austin.

The objective of this proposal is to establish the necessary technology infrastructure associated with the S-FIL process, including system, materials, and template (mask) development. The three-year project will focus on dense contact layers, which are critical in silicon integrated circuit fabrication. The \$36M award includes \$17.6M from NIST and \$19.1M cost sharing from the joint venture participants.

“Molecular Imprints and its joint venture partners are extremely excited to receive this NIST ATP award,” says Dr. S.V. Sreenivasan, co-founder and CTO of MII. “This significant project will help demonstrate how S-FIL technology can address the demanding silicon CMOS lithography requirements.”

About Molecular Imprints Inc.

Molecular Imprints, Inc. develops and manufactures nano-lithography systems for high resolution and for 3-dimensional pattern replication. The company has commercialized a new and unique Step and Flash Imprint Lithography technology (S-FIL), which is a simple step and repeat, room temperature, low pressure, nano-imprint process that has demonstrated sub-20 nanometer resolution. For more information, visit:
www.molecularimprints.com.

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